

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	10	semiconductor and ((dual near5 mask\$4) with (amorphous))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/23 15:04
S2	380	semiconductor and ((mask\$4) with (amorphous and carbon))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/23 15:06
S3	4	semiconductor and (((multiple or multi-layer\$4) near5 mask\$4) with (amorphous and carbon))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/23 15:21
S7	17	semiconductor and ((mask\$4) with (amorphous and carbon)) and damascene and (CMP or (mechanical near3 polish\$4)) and (ARC or anti-reflect\$5 or antireflect\$5 or anti adj reflect\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/24 22:20
S8	3774	((257/758) or (257/760)).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/07/24 22:21
S11	52	(257/758 or 257/760).ccls. and (amorphous same mask\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/24 22:22
S12	290	(257/758 or 257/760).ccls. and (amorphous) and (mask\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/24 22:22
S13	318	(257/758 or 257/760 or 438/671).ccls. and (amorphous) and (mask\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/24 22:23
S14	669	(257/E21.232 or 257/E21.035 or 257/E21.27).ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/24 22:26
S15	134	(257/E21.232 or 257/E21.035 or 257/E21.27).ccls. and amorphous and mask\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/24 22:26